

Nanonex Delivers Advanced Ultra-100 Tool to Columbia University

Princeton NJ, Nov. 13, 2009:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of Nanonex's Ultra-100 to Columbia University. Nanonex is proud to support the leading edge research at the Columbia University.

The Nanonex Ultra-100 is a compact desktop design system that performs cleaning and vapor coating in an integrated single chamber solution. The Ultra-100 capabilities are vacuum cleaning, UV Ozone cleaning, molecular vapor coating with single or multiple chemical vapors. The Ultra-100 is fully automated and user controlled via the front panel.

About Nanonex Corporation

Nanonex is the inventor of "nanoimprint lithography", the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex's patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.